

IN THE CLAIMS:

Claim 1 (Original): A method of fabricating a liquid crystal display device having first and second substrates, the method comprising the steps of:

forming a gate line on the first substrate;

sequentially forming a first insulating layer, an amorphous silicon layer, and a metal layer on the first substrate;

patterning the metal layer to form a data line;

forming a second insulating layer on the data line;

patterning the second insulating layer and the amorphous silicon layer to form a passivation layer and an active layer, respectively;

forming a pixel electrode at a pixel region defined by the gate and data lines;

assembling the first substrate and the second substrate having a black matrix thereon, wherein the black matrix vertically overlaps at least one boundary line defined by different exposures during step-and-repeat exposure processes; and

forming a liquid crystal layer between the first and second substrates.

Claim 2 (Original): The method of claim 1, wherein the boundary line is disposed over the gate line and the data line.

Claim 3 (Original): A method of fabricating a liquid crystal display device having first and second substrates, comprising:

- forming a gate line on the first substrate;
- forming a gate insulating layer on the first substrate including the gate line;
- forming an amorphous silicon layer on the gate insulating layer;
- forming a data line on the amorphous silicon layer;
- forming an insulating layer on the amorphous silicon layer including the data line;
- forming a photoresist layer having first, second, and third portions on the insulating layer, wherein the first portion has a thickness greater than the second portion, and the third portion exposes a portion of the insulating layer;
- selectively removing the insulating layer and the amorphous layer to form a passivation layer on the data line and an active layer below the data line;
- forming a pixel electrode on the gate insulating layer;
- forming a black matrix over the second substrate; and
- assembling the first and second substrates to substantially overlap at least one boundary line and the black matrix in a vertical direction, wherein the boundary lines is defined during step-and-repeat exposures at different times.

Claim 4 (Original) The method of claim 3, wherein the pixel electrode has a stitch line therein.

Claim 5 (Original) The method of claim 3, wherein the gate insulating layer has a stitch line therein.

Claim 6 (Original): The method of claim 3, wherein the exposed portion of the insulating layer vertically overlaps the gate line.

Claim 7 (Canceled).

Claim 8 (Canceled).